

# Preparation of $\text{SrTiO}_3$ single crystals for $\text{TiO}_2$ thin film deposition

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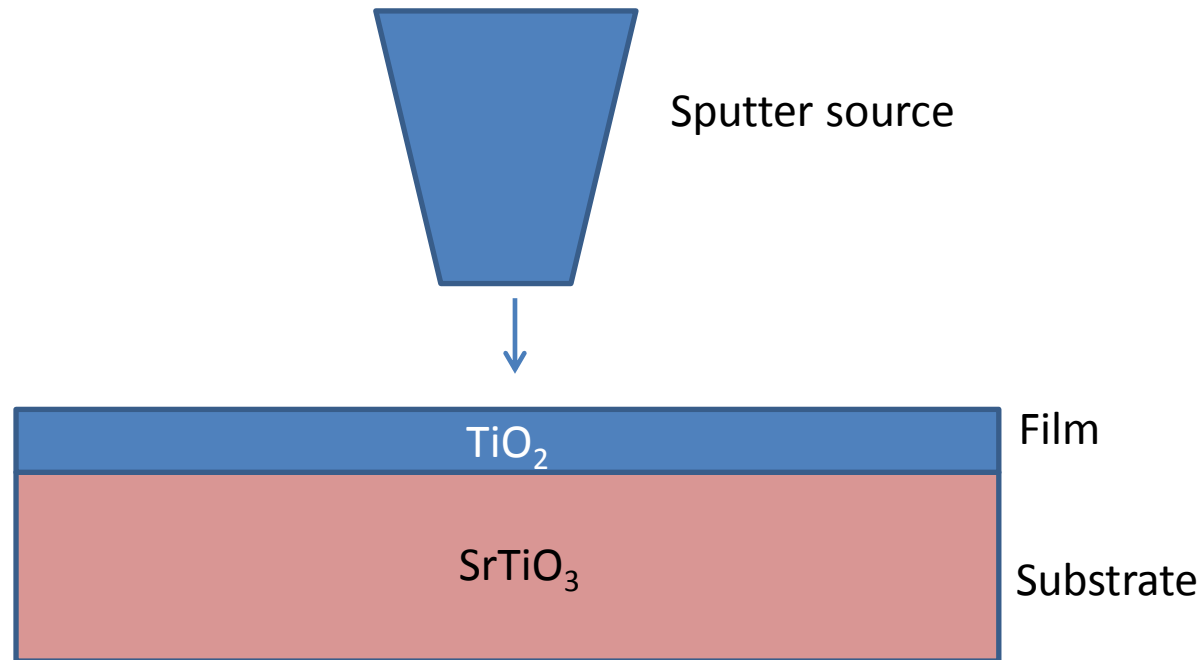


# Outline

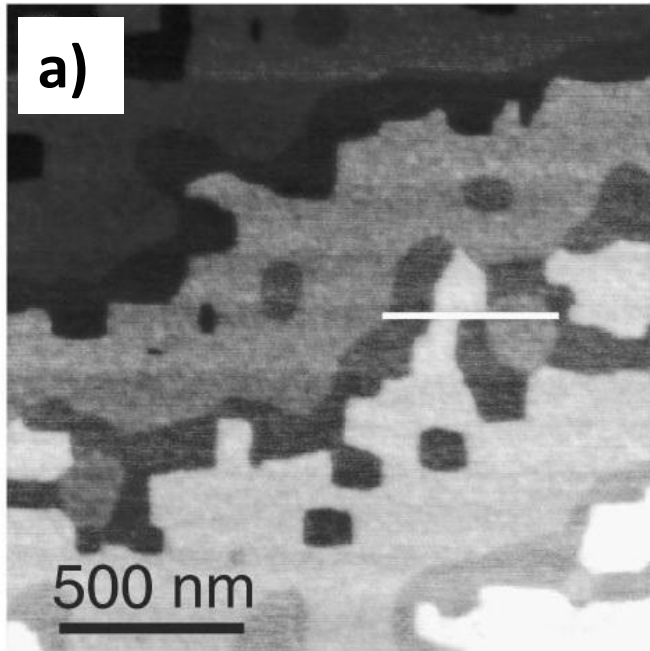
- Motivation
- State of the art
- Workplan
- Results

# Motivation

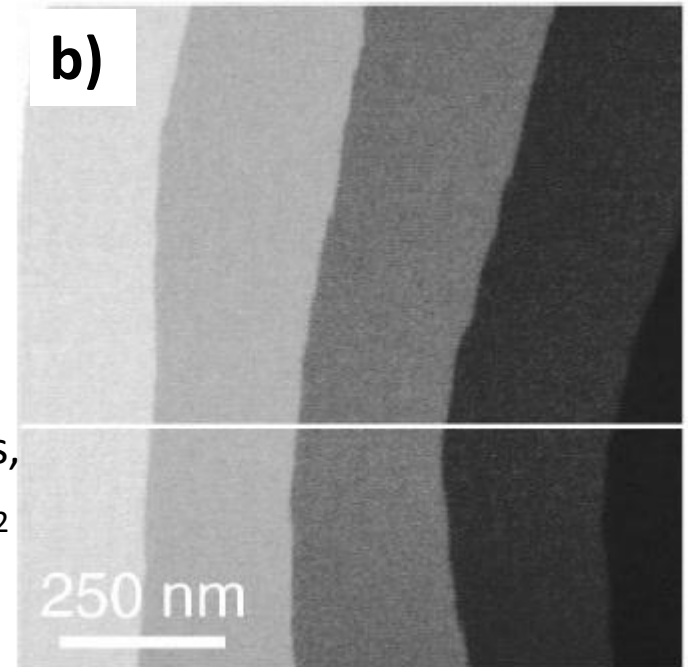
- Creation of regularly shaped atomic like stepped  $\text{SrTiO}_3$  surfaces
- For smooth morphology of  $\text{TiO}_2$
- For epitaxial orientation of  $\text{TiO}_2$



# State of the art



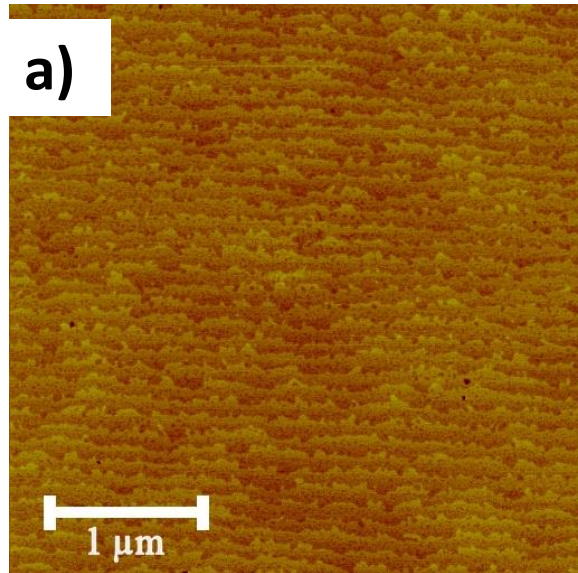
NH<sub>4</sub>F:HF Etching 30s,  
1 hour Annealing O<sub>2</sub>  
atm. 950 C



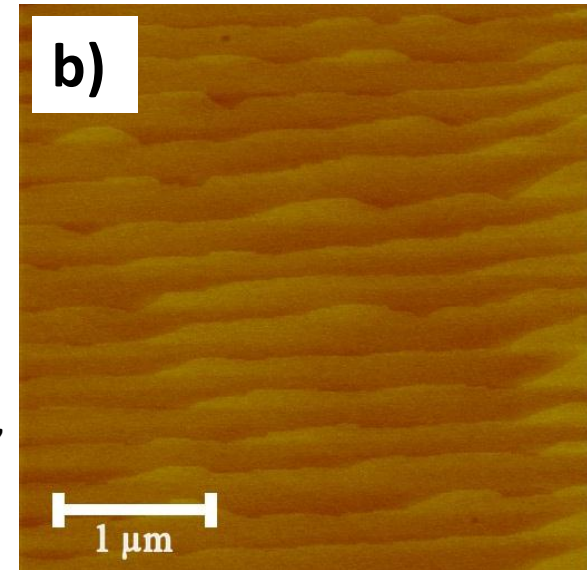
The lattice of SrTiO<sub>3</sub> consists of two sub-lattices of SrO and TiO<sub>2</sub>, layered alternately. To facilitate well controlled epitaxial growth on STO substrates, it is better to have a single surface termination with atomically flat terraces

Quasi-ideal strontium titanate crystal surfaces through formation of strontium hydroxide, *Koster et al.* *APL* 73(1998)20

# State of the art



NH<sub>4</sub>F:HF Etching 40s,  
4 hour Annealing O<sub>2</sub>  
atm. 950 C



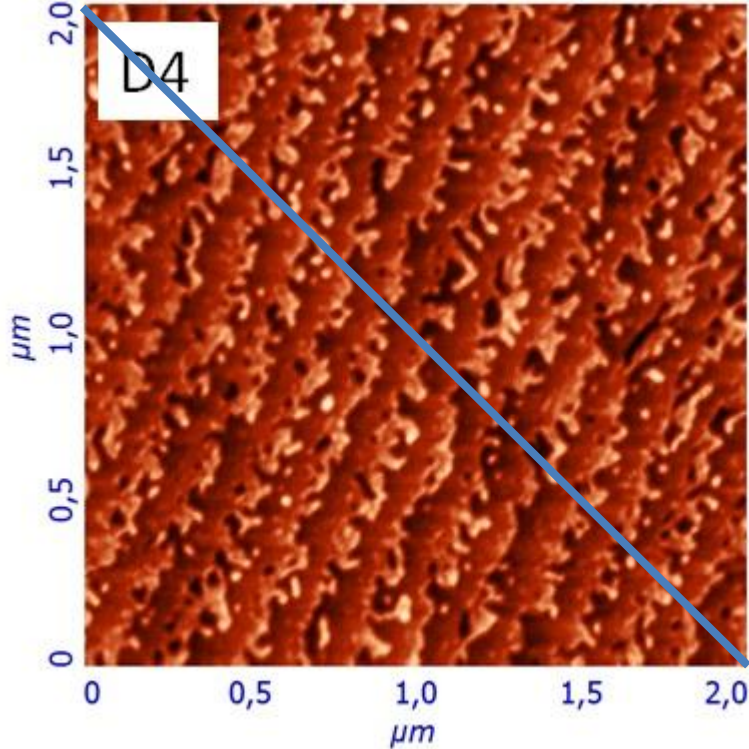
Magnetische Eigenschaften von metallischen Grenzflächen und Strontiumtitanat, *Armin Haase, 2011, Dresden*

# Workplan

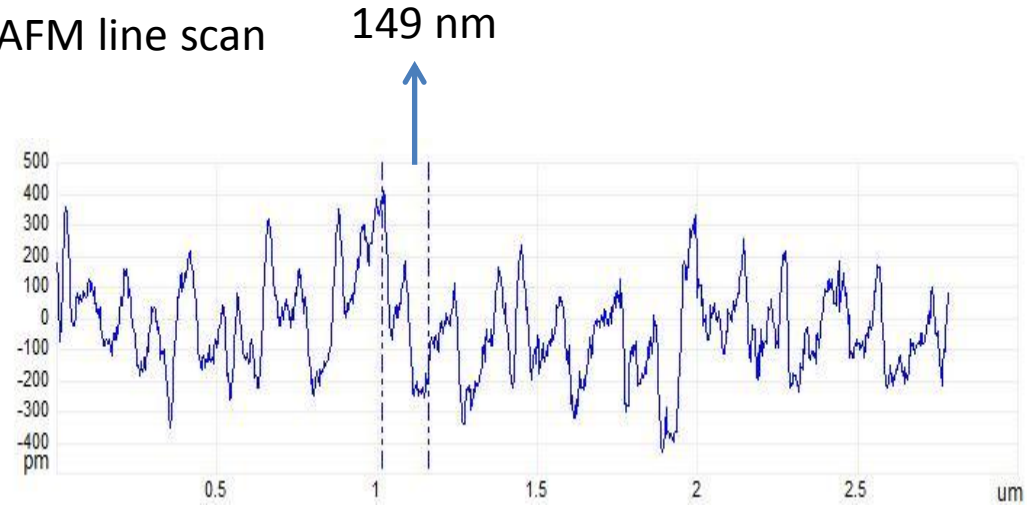
- Cleaning with Deionized water for 10 minutes
- Etching with  $\text{NH}_4\text{F}:\text{HF}=87.5:12.5$ ,  $\text{pH}=5.5$ .
  - Variation of etching time (0 s, 20s, 40s, 60s)
- Annealing in  $\text{O}_2$  atmosphere (7 l/min flow, 950 C)
  - Variation of annealing hold time ( 1h, 4h)
  - Atomic Force Microscopy (AFM)

# Results

AFM image



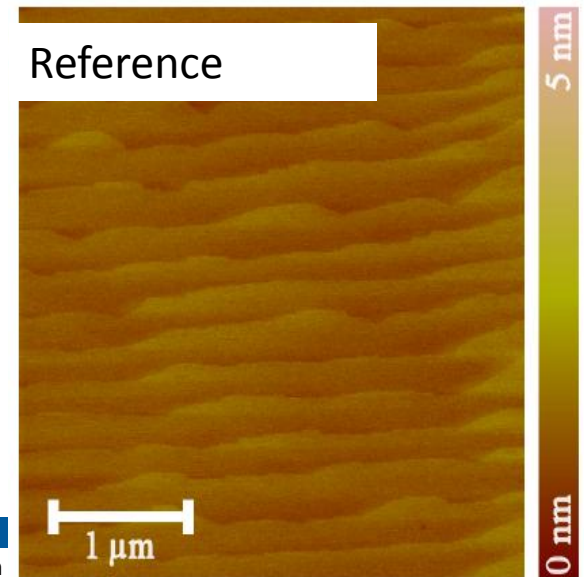
AFM line scan



Sample D4

- No ultrasonic cleaning and no etching
- Annealing: 1 hour

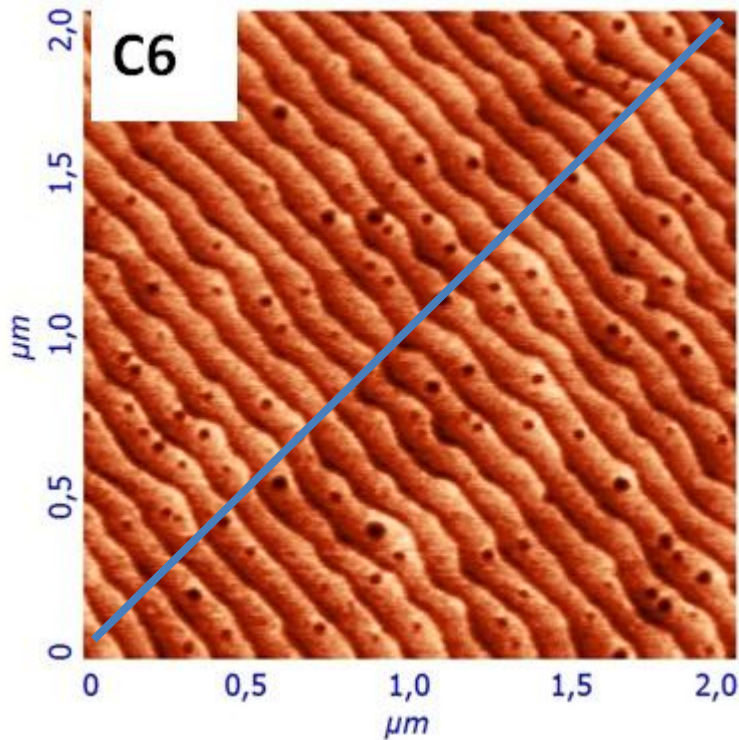
Reference



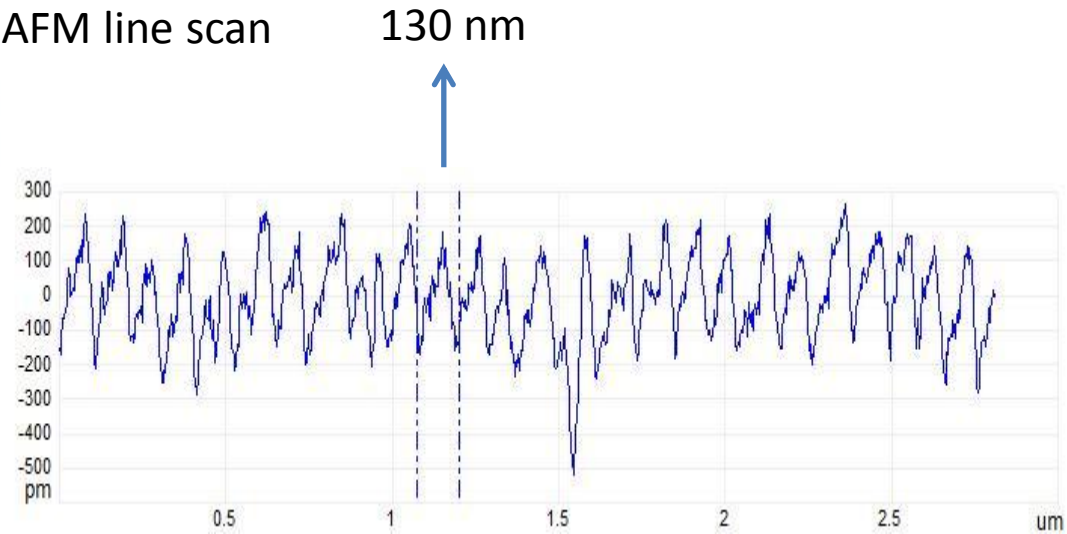


# Results

AFM image

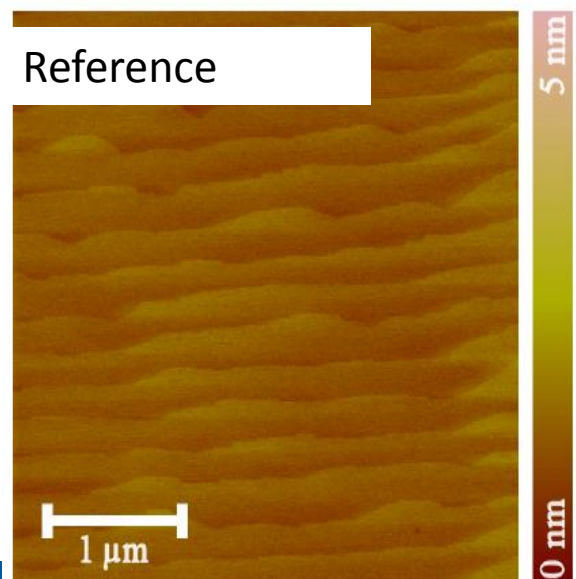


AFM line scan



## Sample C6

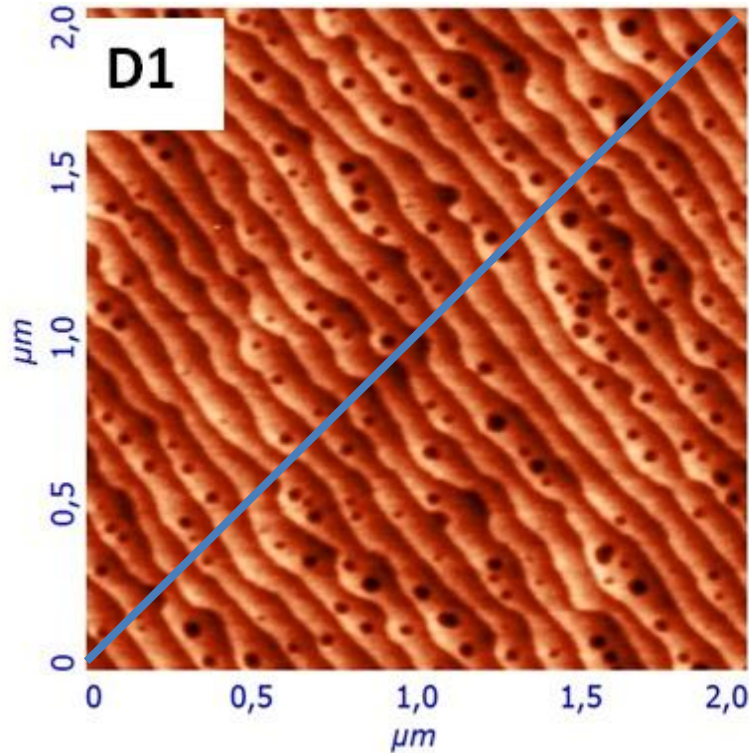
- 10 mins Ultrasonic cleaning, 20 s etching
- Annealing: 1 hour



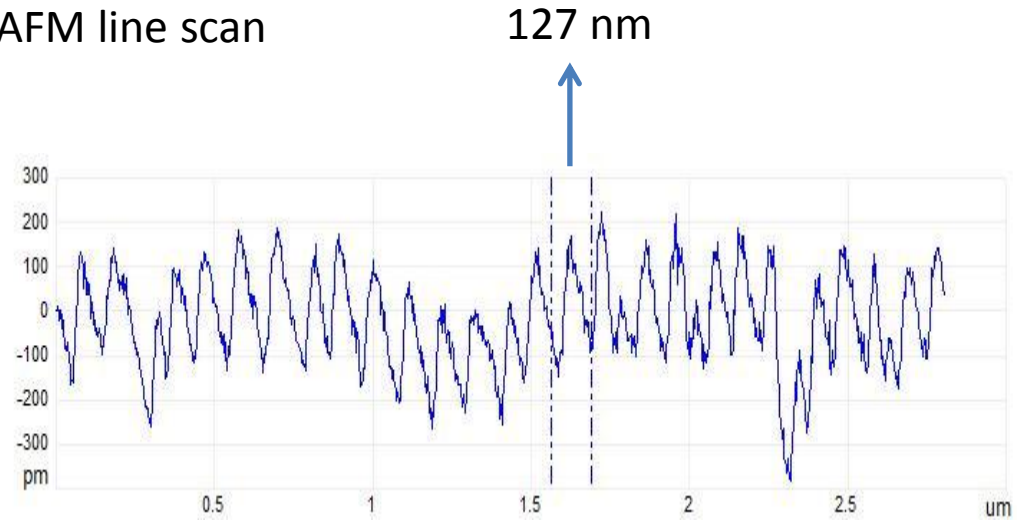


# Results

AFM image



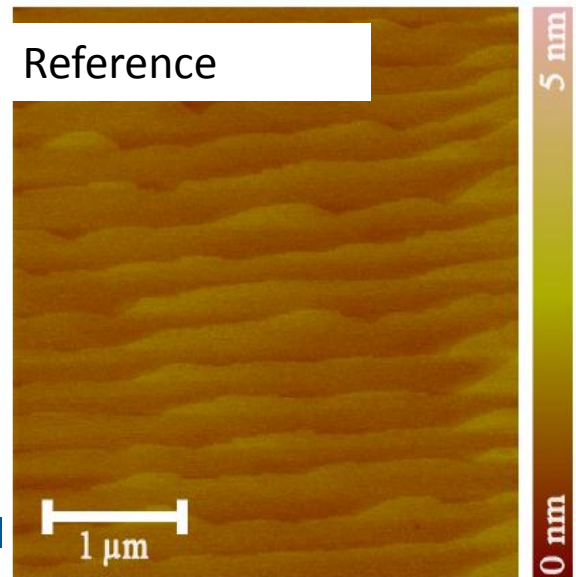
AFM line scan



## Sample D1

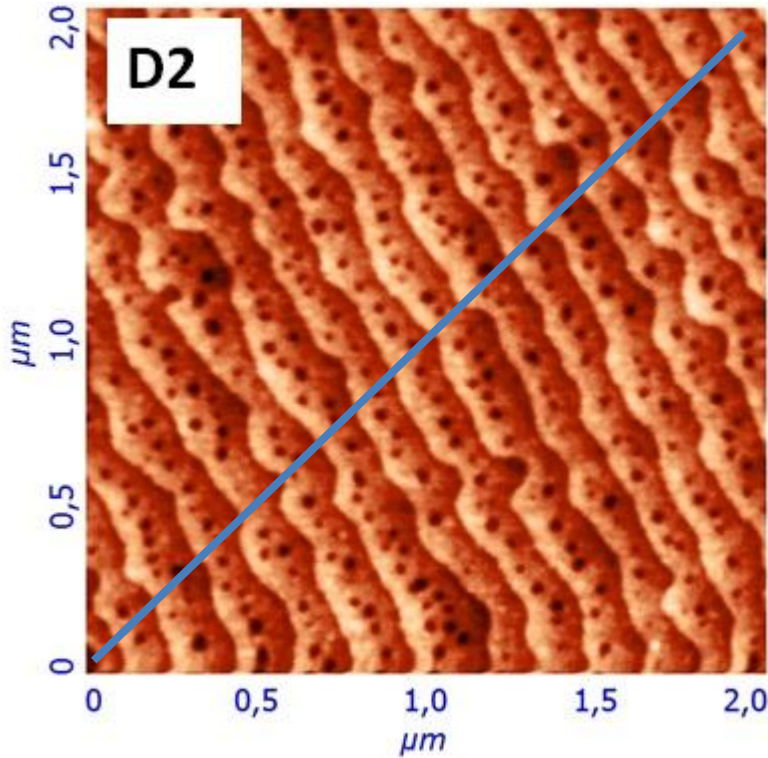
- 10 mins Ultrasonic cleaning, 40 s Etching
- Annealing: 1 hour

Reference

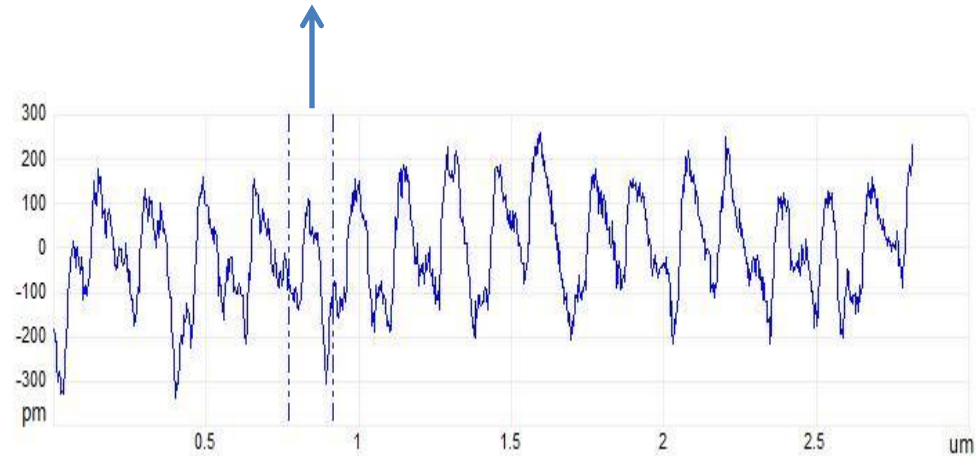


# Results

AFM image



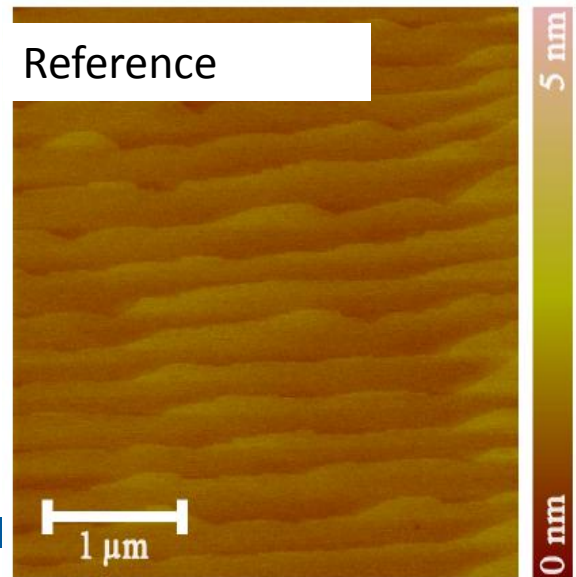
AFM line scan 144 nm



## Sample D2

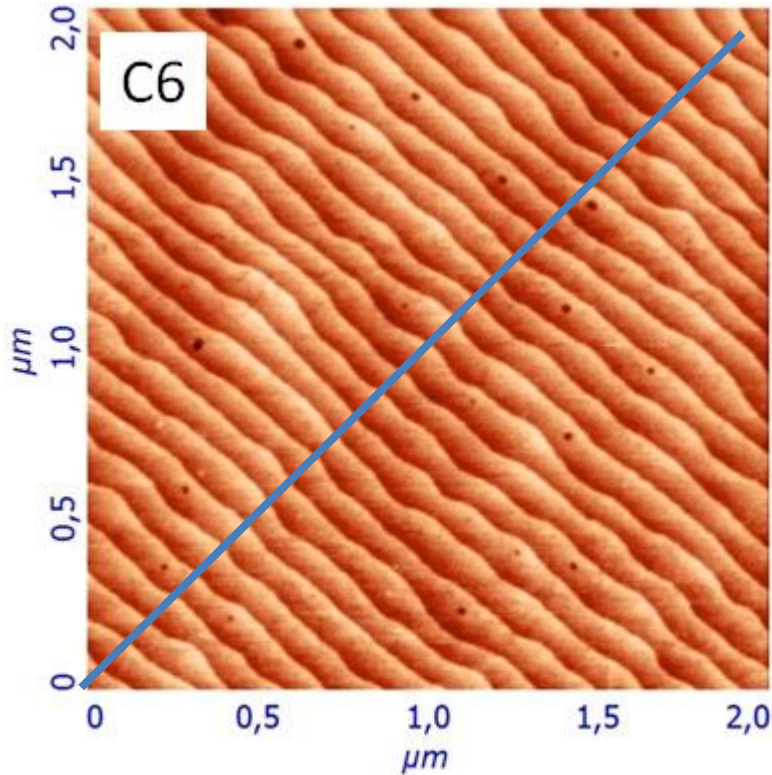
- 10 mins Ultrasonic cleaning, 60 s etching
- Annealing: 1 hour

Reference

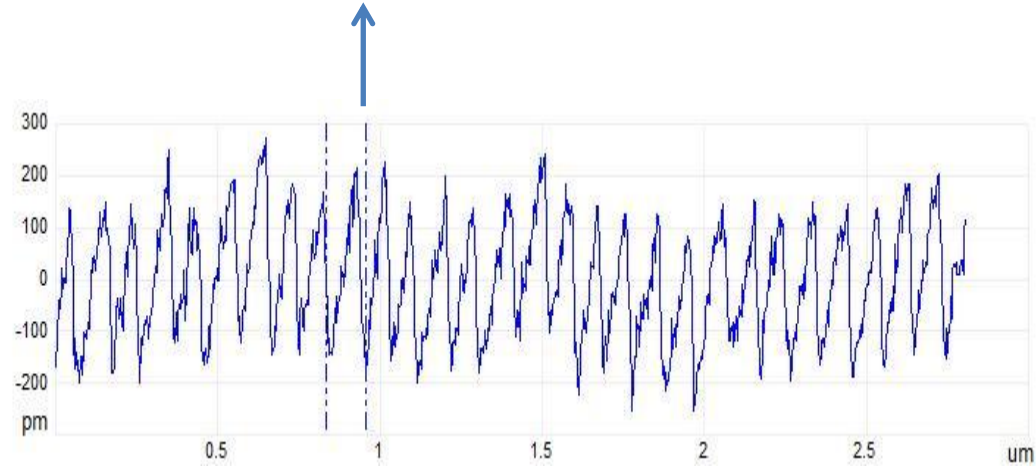


# Results

AFM image



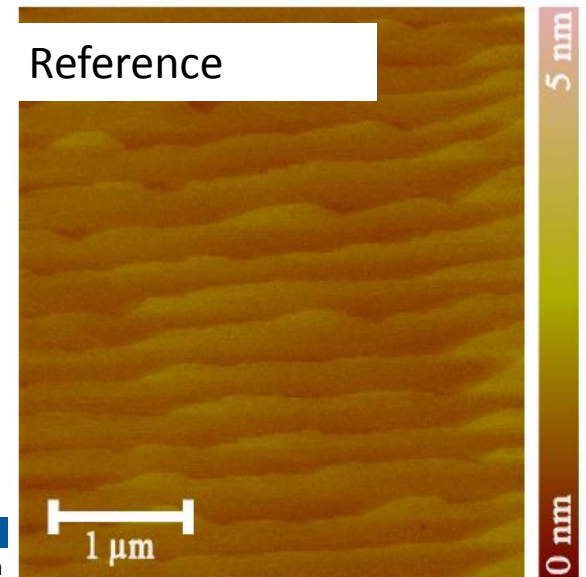
AFM line scan 122 nm



Sample C6

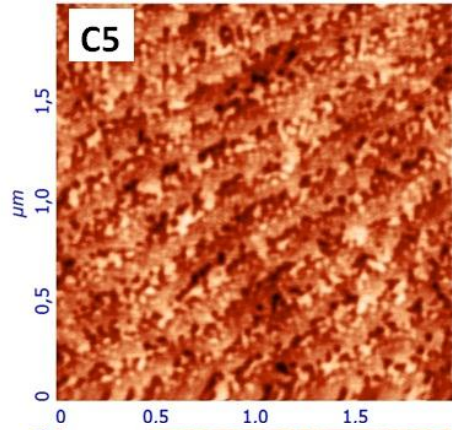
- 10 mins Ultrasonic cleaning, 20 s etching
- Annealing: 4 Hour

Reference

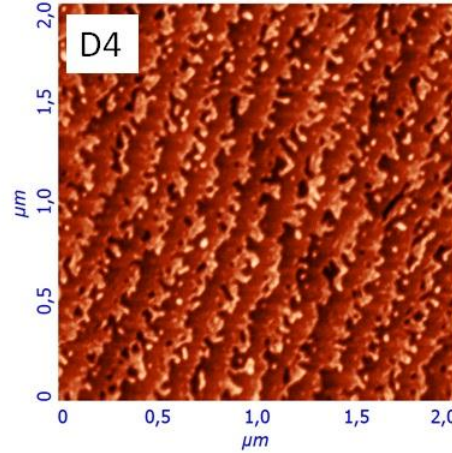




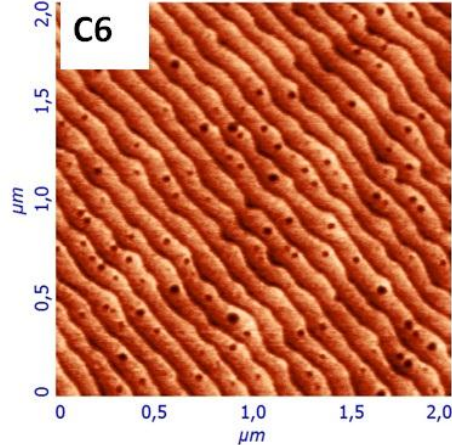
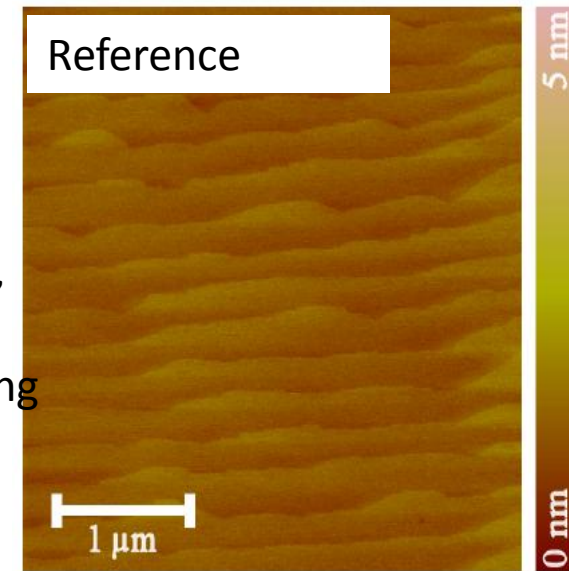
# Results



No etching,  
no annealing



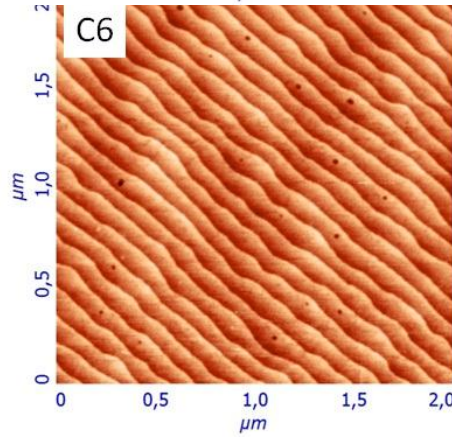
No etching,  
1 hour annealing



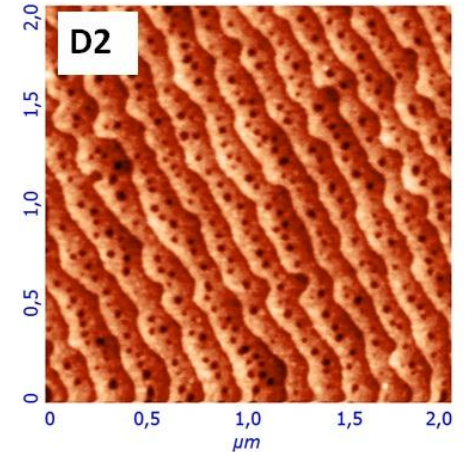
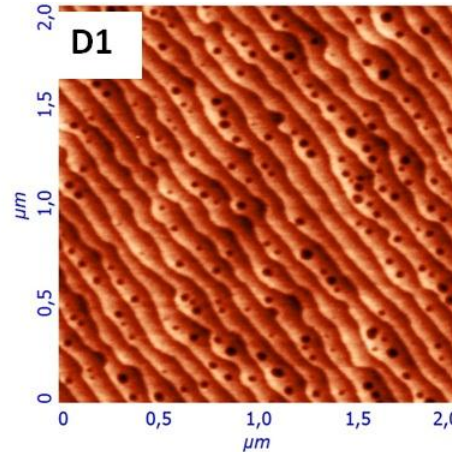
20 s etching,  
1 hour annealing

40 s etching,  
1 hour annealing

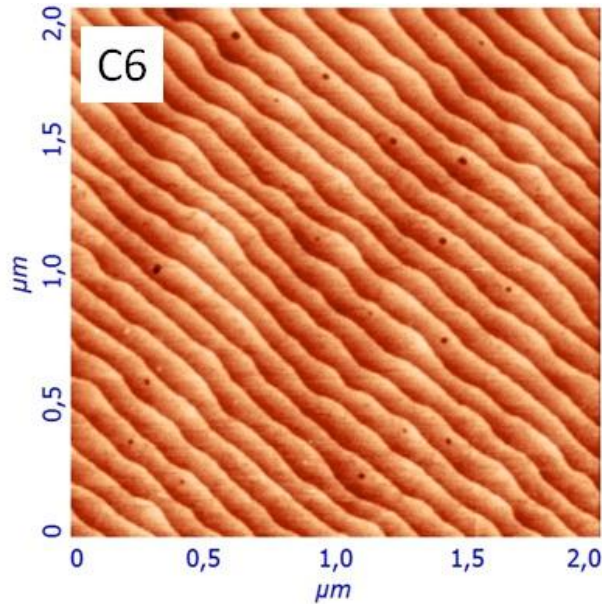
60 s etching,  
1 hour annealing



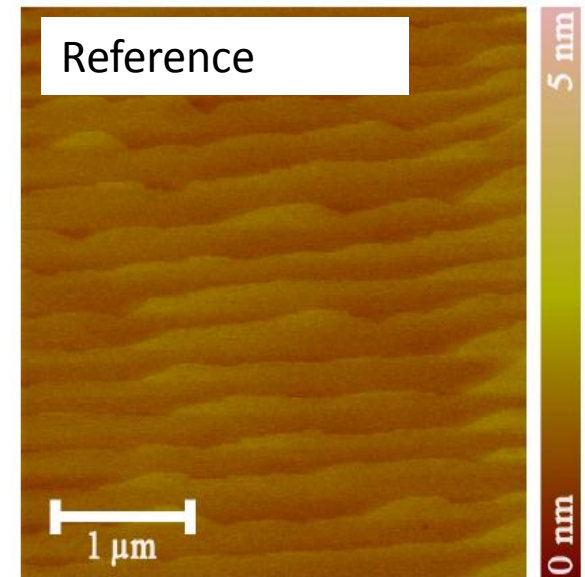
20 s etching,  
4 hour annealing



# Results



4 hour annealing



Optimized Results: 10 minutes ultrasonic cleaning, 20s etching and 4 hours annealing!!!